

Stress relaxation mechanism by strain in the Si-SiO₂ system and its influence on the interface properties
Kropman, Daniel; Mellikov, Enn; Kärner, Tiit; Laas, Tõnu; Medvid, Arthur; Onufrijevs, Pavels; Dauksta, Edvins Solid state phenomena 2011 / p. 259-262